The need

Monitoring particle contaminants is crucial in the semiconductor industry and clean industries in general.

Even submicron foreign particles can be devastating to production process yield. Yet, current methods for measuring particles on parts are complicated, time-consuming, and require reprocessing after the test.

To check the entire surface of parts while keeping them ready for use, parts testing processes need to be reliable, repeatable, fast, and convenient.

Our solution

Our innovative device measures the particle level on almost any part using a non-destructive test method on a complete sample body.

The particle measurement is not influenced by external environmental factors such as the operator, water source, or geographical location.

Our device – PARTi Particle Control and Monitoring System

Technology is based on counting removed particles by airflow energy.

Particle measurement range of 0.1-5.0µ

Capability to collect particles for material analysis

Counting released particles from different geometric shapes, surfaces, and a wide range of materials and consumables

Nondestructive test—parts are ready for use, no need for additional treatment after testing.

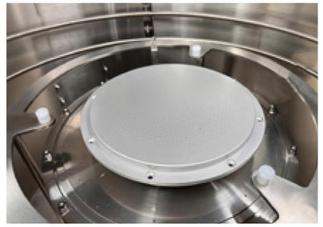
Short test time – just a few minutes

The perfect solution for “finished assembly

Fixtures and tested parts

Complex shapes

FOUP

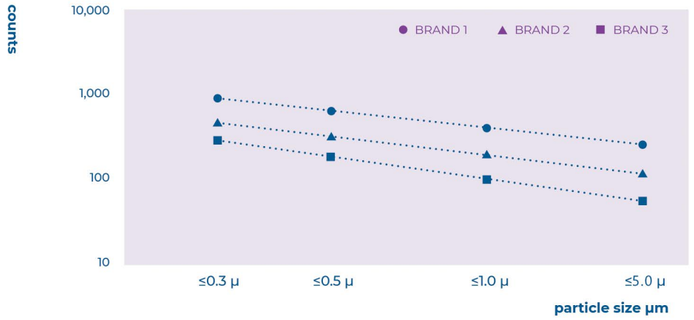


Shower Head

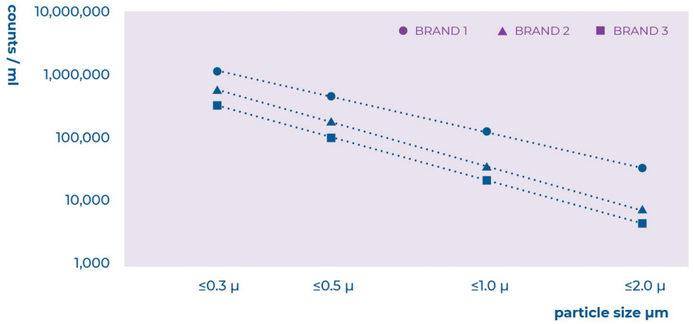
Comparison between LPC and PARTi

Comparative NitrileGlove Tests

PARTi – cumulative particles count



LPC – cumulative counts / ml



SCAN FOR PRODUCT MOVIE